L Number	Hits	Search Text	DB	Time stamp
-	79	first$ near10 (HF or fluoric) same (ozone or "o.sub.3" or "o3")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/08 16:25
-	3	first$ near10 (HF or fluoric) same (ozone or "o.sub.3" or "o3") same HCl	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/03 15:40
-	2	20010003680.pn.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/03 15:42
-	15	"1005072"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/03 15:42
-	298	(HF or fluoric) same (ozone or "o.sub.3" or "o3") same hcl	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/03 16:12
-	45	(HF or fluoric) same (ozone or "o.sub.3" or "o3") same hcl same wafer	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/03 16:25
-	81	(HF or hydrofluoric or fluoric) same (ozone or "o.sub.3" or "o3") same hcl same treat$	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/03 16:29
-	54	(HF or hydrofluoric or fluoric) same (ozone or "o.sub.3" or "o3") same hcl and 438/$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/03 16:33
-	92	(HF or hydrofluoric or fluoric) same (ozone or "o.sub.3" or "o3") same sequen$	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/03 16:33
-	58	(HF or hydrofluoric or fluoric) near20 (ozone or "o.sub.3" or "o3") same sequen$	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/03 16:42
-	131	(ozone or "o.sub.3" or "o3") same (hcl or hydrochloric) same sequen$	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/03 16:42
-	245	(Ozone or "o.sub.3") same (hcl or hydrochloric) and 438/$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/08 16:26
-	23	(Ozone or "o.sub.3") same (hcl or hydrochloric) same rins$ and 438/$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/08 16:31
-	6	(Ozone or "o.sub.3") same (hcl or hydrochloric) same hydrophil$ and 438/$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/08 16:27

-	102	(Ozone or "o.sub.3") same (hcl or hydrochloric) same etch$ and 438/$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/08 16:31
-	48	(Ozone or "o.sub.3") same (hcl or hydrochloric) same etch$ and HF and 438/$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/08 16:35
-	0	(Ozone or "o.sub.3") same (hcl or hydrochloric) same etch$ and HF and 438/734$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/08 16:35
-	3	(Ozone or "o.sub.3") same (hcl or hydrochloric) and 438/734.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/08 16:36
-	13	(Ozone or "o.sub.3") and (hcl or hydrochloric) and 438/734.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/08 16:43
-	42	(Ozon$ or "o.sub.3") same (hcl or hydrochloric) same follow$4 and 438/$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/08 16:44
-	26	(Ozon$ or "o.sub.3") same (hcl or hydrochloric) same follow$4 same solution and 438/$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/08 16:50
-	24	(hcl or hydrochloric) same solution same hydrophil$5 and 438/$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/08 16:54
-	381	(hcl or hydrochloric) same solution same oxide near4 (layer or film) and 438/$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/08 16:54
-	111	(hcl or hydrochloric) near10 etch$4 same solution same oxide near4 (layer or film) and 438/$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/08 16:56
-	109	(hcl or hydrochloric) near10 etch$4 near10 oxide near4 (layer or film) and 438/$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/08 17:01
-	78	(hcl or hydrochloric) near5 (solution or acid) near10 etch$4 near10 oxide near4 (layer or film) and 438/$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/08 17:11
-	99	(sequenc$4 or sequent$6) near10 clean$4 same (ozone or "o.sub.3")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/08 17:11
-	26	(sequenc$4 or sequent$6) near10 clean$4 same (ozone or "o.sub.3") same solution	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/08 17:21

-	92	(sequenc$4 or sequent$6) same (ozone or "o.sub.3") same solution same (hcl or hydrochloric)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/08 17:24
-	2	((sequenc$4 or sequent$6) same (ozone or "o.sub.3") same solution same (hcl or hydrochloric)) and 438/$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/08 17:22
-	10	(sequenc$4 or sequent$6) same (ozone or "o.sub.3") same solution same (hcl or hydrochloric) same (etch$ or clean$)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/09 10:13
-	146590	(sequenc$4 or sequent$6) near4 process$5	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/09 10:16
-	7621	((sequenc$4 or sequent$6) near4 process$5) and 438/$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/09 10:17
-	227	((sequenc$4 or sequent$6) near4 process$5) and 438/$.ccls. and (ozone and "o.sub.3")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/09 10:18
-	195	((sequenc$4 or sequent$6) near4 process$5) and 438/$.ccls. and (ozone or "o.sub.3") and (hcl or hydrochlor$)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/09 10:18
-	51	((sequenc$4 or sequent$6) near4 process$5) and 438/$.ccls. and (ozone or "o.sub.3") same (hcl or hydrochlor$)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/09 10:19
-	23	((sequenc$4 or sequent$6) near4 process$5) same ("without" near5 rins$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/09 10:19